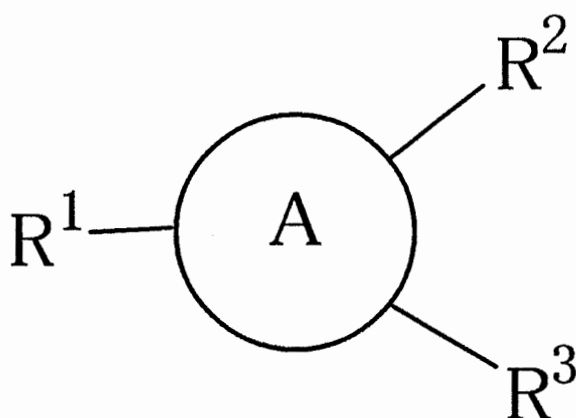


## ABSTRACT

There is provided a resist underlayer film forming composition for lithography.

A resist underlayer film forming composition for lithography, comprising: as a silane: at

- 5 least one among a hydrolyzable organosilane, a hydrolysis product thereof, and a hydrolysis-condensation product thereof, wherein the silane includes a silane having a cyclic organic group containing as atoms making up the ring, a carbon atom, a nitrogen atom, and a hetero atom other than a carbon atom and a nitrogen atom. The hydrolyzable organosilane may be a hydrolyzable organosilane of Formula (1):



Formula (1)

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(in Formula (1), at least one group among R<sup>1</sup>, R<sup>2</sup>, and R<sup>3</sup> is a group in which a -Si(X)<sub>3</sub> group is bonded to a C<sub>1-10</sub> alkylene group, and the other group(s) among R<sup>1</sup>, R<sup>2</sup>, and R<sup>3</sup> is(are) a hydrogen atom, a C<sub>1-10</sub> alkyl group, or a C<sub>6-40</sub> aryl group; a ring A is a cyclic organic group of a 5- to 10-membered ring containing as atoms making up the ring, a carbon atom, at least one nitrogen atom, and further containing a sulfur atom or an oxygen atom; and X is an alkoxy group, an acyloxy group, or a halogen atom).

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